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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10071809	FILING DATE 02/07/2002	CLASS 257	SUBCLASS 689	GAU 2844	1765	EXAMINER Pen-D
**APPLICANTS: Wang Tinghao;						
**CONTINUING DATA VERIFIED: THIS APPLICATION IS A CON OF 09/342,335 06/29/1999 q/a						
** FOREIGN APPLICATIONS VERIFIED:						
PG-PUB <input checked="" type="checkbox"/> DO NOT PUBLISH <input type="checkbox"/> RESCIND <input type="checkbox"/>						
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiners's initials				ATTORNEY DOCKET NO 10200-16		
TITLE : Method for selectively etching silicon and/or metal silicides						
U.S. DEPT. OF COMM. / PAT. & TM. PTO-435L (Rev. 12-94)						

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED			
		Assistant Examiner	Total Claims		
			Print Claim for O.G.		
ISSUE FEE		Primary Examiner	DRAWING		
Amount Due	Date Paid		Sheets Drwg.	Figs. Drwg.	Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	Application Examiner		
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